## **ELECTRONIC INFORMATION DISCLOSURE STATEMENT**

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

HIGH-PRESSURE PROCESSING CHAMBER FOR A SEMICONDUCTOR WAFER

Application Number: 10/680783

Confirmation Number: 5859

First Named Applicant: William Jones

Attorney Docket Number:

Art Unit: Examiner:

Search string: (3623627 or 4426358 or 4574184 or 5374829 or 5474410 or 5879459 or 6048494

or 6062853 or 6089377 or 6406782 or 20010050096 ).pn

## **US Patent Documents**

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	3623627	1969-08-22	Alan S. Bolton			
	2	4426358	1984-01-17	Johansson			
	3	4574184	1986-03-04	Wolf et al.			
	4	5374829	1994-12-20	Sakamoto et al.			
	5	5474410	1995-12-12	Ozawa et al.			
	6	5879459	1999-03-09	Gadgil et al.			
	7	6048494	2000-04-11	Annapragada			
	8	6062853	2000-05-16	Shimazu et al.		·	
	9	6089377	2000-07-18	Shimazu			
	10	6406782	2000-06-18	Johnson et al.	B2	·	

## **US Published Applications**

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
	1	20010050096	2001-12-13	Costantini et al.	<b>A</b> 1		

## **Signature**

Examiner Name	Date

